

Replacement Sheet 1 of 2
 Applicant: Bera, et al.
 Title: APPARATUS FOR CONTROLLING
 GAS FLOW IN A SEMICONDUCTOR
 SUBSTRATE PROCESSING CHAMBER
 Serial No. 10/821,310

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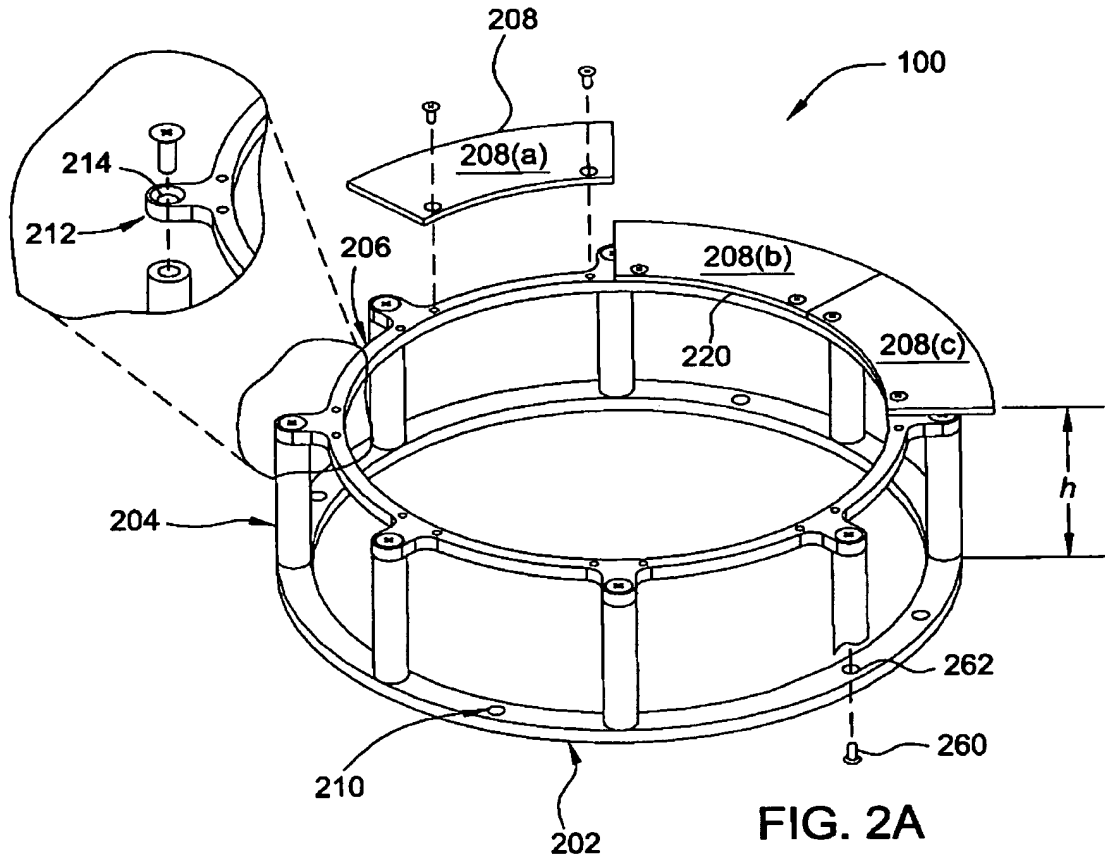


FIG. 2A

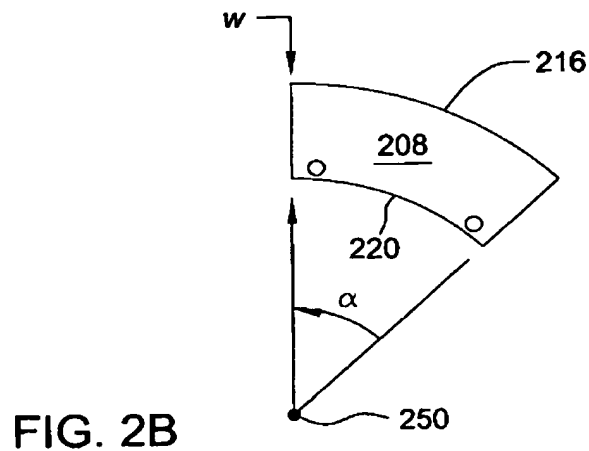


FIG. 2B

